NETZSCH
Proven Excellence.

Technical Specification (subject to change)

		NanoTR	*PicoTR*
Pump Laser	Pulse width Wave length Beam diameter	1 ns 1550 nm 100 µm	0.5 ps 1550 nm 45 µm
Probe Laser	Pulse width Wave length Beam diameter	contiuous 785 nm 50 µm	0.5 ps 775 nm 25 µm
Measurement items		Thermal diffusivity and effusivity, interfacial resistance	
Sample Film Thickness (RF method)	Resin Ceramics Metal	30 nm ... 2 µm 300 nm ... 5 µm 1 µm ... 20 µm	10 nm ... 100 nm 10 nm ... 300 nm 100 nm ... 900 nm
Sample Film Thickness (FF method)		Thicker than 1 µm	Thicker than 100 nm
Substrate	Material Size Thickness	Opaque/Transparent 10 ... 20 mm square 1 mm max.	
Thermal diffusivity	Range	0.01 ... 1000 mm^2/s	
	Accuracy	± 6.2% with 40 min measurement time, for CRM 5808A in RF Mode, 400 nm thickness	
	Repeatability	± 5%	
Software		Calculation of thermal properties, multilayer analysis, database	